



Session Title:	[TA2] Advanced Atomic Scale Thin Films IV
Session Date:	November 21 (Tue.), 2023
Session Time:	10:20-12:00
Session Room:	Room A (Capri Room, 2F)
Session Chair:	Prof. Jin-Seong Park (Hanyang Univ., Korea)

[TA2-1] [Invited] 10:20-10:50

Challenges and Requirements of ThinFilm Technology in the Era of Moore's Law Extension and Beyond

Jinhee Park (SK hynix, Korea)

[TA2-2] [Invited] 10:50-11:20

Area-Selective Deposition on Features with Nanoscale Dimensions for Semiconductor Device Manufacturing

Annelies Delabie, Jan-Willem Clerix, Kaat van Dongen, Jyoti Sinha, Laura Nyns , Rachel Nye (imec, Belgium), Gregory N. Parsons (North Carolina State Univ., USA), Jean-François de Marneffe, and Johan Swerts (imec, Belgium)

[TA2-3] [Invited] 11:20-11:40

Combined Atomic Layer Deposition and Etching Process towards Advanced Atomic Level Patterning

Woo-Hee Kim (Hanyang Univ., Korea)

[TA2-4] [Invited] 11:40-12:00

The Improvement of Interfacial Properties of MIM Capacitors

Woongkyu Lee (Soongsil Univ., Korea)